

## SUBSTRATE PROCESSING DEVICE

### ABSTRACT

A substrate processing device includes a first chamber and a second chamber. The second chamber includes a circulation space defined in a wall of the second chamber to allow a gas to circulate in a direction in which the wall extends, at least one supply port connecting with the circulation space to supply the gas, and at least one outlet connecting with the circulation space to discharge the gas to at least one of an inside or an outside of the second chamber.

5

Fig. 4